

ZrO₂

Oxide ZIRCONIUM SPUTTERING TARGET

Zirconium oxide sputtering target contains Zr and O. The main use of zirconia is in the production of hard ceramics, such as in dentistry, with other uses including as a protective coating on particles of titanium dioxide pigments, as a refractory material, as a thin film coating material, in insulation, fuel cell, abrasives and enamels. Zirconia sputtering target is used for thin film deposition, typically for fuel cell, decoration, semiconductor, display, LED and photovoltaic devices, glass coating, etc.

Quick Facts

Product	:	Zirconium Oxide Sputtering Target
Stock No	:	NS6130-10-1327
CAS	:	1314-23-4
Backing Plate	:	(As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1327	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
ZrO ₂	123.22g/mol	2700°C



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CERTIFIED COMPANY



High Purity
SPUTTERING
TARGET